

	Type	Hits	Search Text
1	BRS	2054	(exposure adj2 apparatus) and laser and ultraviolet
2	BRS	5	(exposure adj2 apparatus) and laser and ultraviolet and (optical adj2 modulat\$5) and (optical adj2 amplif\$8) and (wavelength adj2 conver\$6)
3	BRS	37	owa-soichi.in.
4	BRS	16	ohtsuki-tomoko.in.
5	BRS	505	laser and (lithography or photolithography) and (wavelength adj2 conver\$6)
6	BRS	46	laser and (lithography or photolithography) and (wavelength adj2 conver\$6) and (optical adj2 modulat\$5) and (optical adj2 amplif\$8)

	DBs	Time Stamp
1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:58
2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:00
3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:02
4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 11:01
5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 12:14
6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:21

	Type	Hits	Search Text
7	BRS	34	laser and (lithography or photolithography) and (wavelength adj2 conver\$6) and modulat\$5 and (fiber adj2 amplif\$8)
8	BRS	14125	(exposure adj2 (apparatus or device)).ti.
9	BRS	732	(exposure adj2 (apparatus or device)).ti. and laser and ultraviolet
10	BRS	513	(exposure adj2 (apparatus or device)).ti. and laser and ultraviolet and (lithography or photolithography)
11	BRS	61	(exposure adj2 (apparatus or device)).ti. and laser and ultraviolet and (lithography or photolithography) and (fiber adj2 amplif\$8) and (nonlinear near2 crystal)
12	BRS	96	(exposure adj2 (apparatus or device)).ti. and laser and ultraviolet and (lithography or photolithography) and (fiber adj2 amplif\$8)

	DBs	Time Stamp
7	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:23
8	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:27
9	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:28
10	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:45
11	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:47
12	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:48

	Type	Hits	Search Text
13	BRS	64	(exposure adj2 (apparatus or device)).ti. and laser and ultraviolet and (lithography or photolithography) and (nonlinear near2 crystal)

	DBs	Time Stamp
13	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 10:57